

Electronic Patent Application Fee Transmittal

Application Number:	10688045			
Filing Date:	17-Oct-2003			
Title of Invention:	Fully dry, Si recess free process for removing high k dielectric layer			
First Named Inventor/Applicant Name:	Huan-Just Lin			
Filer:	David M. Odell/Denise Wilson			
Attorney Docket Number:	2003-0065/24061.508			
Filed as Large Entity				
Utility Filing Fees				
Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Basic Filing:				
Pages:				
Claims:				
Miscellaneous-Filing:				
Petition:				
Patent-Appeals-and-Interference:				
Filing a brief in support of an appeal	1402	1	500	500
Post-Allowance-and-Post-Issuance:				
Extension-of-Time:				

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Total in USD (\$)				500